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[54] **USE OF MIXTURES OF ETHYL LACTATE AND N-METHYL PYROLLIDONE AS AN EDGE BEAD REMOVER FOR PHOTORESISTS**

[75] Inventors: **William C. Nelson**, Whitehouse Station; **Octavia Lehar**, Flemington, both of N.J.

[73] Assignee: **Clariant Finance (BVI) Limited**, Virgin Islands (Br.)

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Related U.S. Application Data

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[52] **U.S. Cl.** **430/326**; 430/192; 430/325; 430/326; 430/330; 430/331

[58] **Field of Search** 430/325, 326, 430/331, 192, 330

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Primary Examiner—John S. Chu
Attorney, Agent, or Firm—Sangya Jain

[57] **ABSTRACT**

The invention provides a process for removing unwanted photoresist material from the periphery of a photoresist-coated substrate using a solvent composition of ethyl lactate and N-methyl pyrollidone, where the amount of N-methyl pyrollidone ranges from about 3% to about 20% by weight of the total composition, and where the solvent composition has a flash point of greater than 100° F. (38° C.), has an odor threshold value greater than 5000, is effective as both a backside and topside edge bead remover and can effectively remove the edge bead from an unbaked or baked photoresist film.

14 Claims, No Drawings